



## **PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Shunichi SEKI et al.

Application No.: 09/423,969

Filed: November 17, 1999

For: THIN FILM PATTERNING SUBSTRATE AND SURFACE TREATMENT

THEREFOR

Group Art Unit:

Examiner:

Docket No.:

2814

Anh D. Mai

104741

ri Paramanan

RESPONSE TO RESTRICTION REQUIREMENT

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

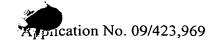
In reply to the Restriction Requirement mailed October 2, 2001, Applicants provisionally elect Group I, claims 1-29, 48, 69-71, 73 and 75-79, drawn to a semiconductor device, classified in class 257, subclass 79<sup>+</sup>, with traverse.

It is also respectfully submitted that the subject matter of all claims 1-80 is sufficiently related that a thorough search for the subject matter of any one group of claims would encompass a search for the subject matter of the remaining claims. Thus, it is respectfully submitted that the search and examination of the entire application could be made without serious burden. See MPEP §803 in which it is stated that "if the search and examination of the entire application can be made without serious burden, the Examiner must examine it on the merits even though it includes claims to distinct or independent inventions" (emphasis added). It is respectfully submitted that this policy should apply in the present application in order to avoid unnecessary delay and expense to Applicants and duplicative examination by the Patent Office.

P. Walk 11-7-01

NOV -5 2001





Thus, withdrawal of the Restriction Requirement is respectfully requested.

Respectfully submitted,

James A. Oliff Registration No. 27,075

Eric D. Morehouse Registration No. 38,565

JAO:EDM/gam

Date: November 1, 2001

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461

÷.